SUPPLEMENTAL MATERIAL

Realizing Chemical Codoping in TiO₂

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The supplemental material provides both experimental and theoretical details, including SEM, TEM, and XRD patterns and some references.

Part 1: Experimental Details

1. Chemical synthesis

All chemicals were used as received without further purification. Titanium (TTIP) was used as the titanium source. Trioctylphosphine (TOP) and urea were chosen as precursors for the phosphorus and nitrogen doping. Both urea and NH_3 have been used as N sources for TiO₂ doping in earlier studies^{1,2}. Urea is chosen in this work due to its ease of handling and its environmental-friendly nature. The choice of P source is another key factor

for the success of the N-P chemical codoping. TOP was used in earlier work as a P source for low-temperature conversion of metals into metal phosphides³. It is therefore chosen here, since the similarity of the oxidation state of the P source to the target environment (i.e., P^{3-}) is necessary.

The as-prepared codoped TiO_2 sample with sequential doping of nitrogen followed by phosphorous was labeled as NP-TiO₂, while the one with reverse doping order was labeled as PN-TiO₂. Accordingly, the phosphor or nitrogen monodoped TiO₂ samples were labeled as $P-TiO_2$ and $N-TiO_2$, respectively. The first process is the synthesis of pure anatase TiO_2 powder⁴. 0.3 ml TTIP was dissolved in 12 ml anhydrous ethanol. The solution was stirred magnetically for several minutes, and then 1 ml nitric acid was added to adjust the acidity of the solution in order to form the gels slowly. At room temperature 3 ml deionized water was added dropwise to the solution under vigorous stirring. The mixture was hydrolyzed in a water bath at 80 °C for 24 h to form a white gel precipitate, and then hydrothermally treated in a Teflon-lined autoclave at 175 $^{\circ}$ C for 3 h to obtain the anatase structure of TiO₂⁵. As a result, the powder sample was obtained by drying in air at 60 °C. N-TiO₂ was obtained by mixing 0.6 g urea with deionized water during hydrolytic synthesis of TiO₂, PN-TiO₂ was synthesized by mixing 0.6 g urea and P-TiO₂ nanoparticles into a high-pressure autoclave with ethanol as a supercritical fluid and heating at 190 $\,^{\circ}$ C for 5 h. P-TiO₂ and NP-TiO₂ were obtained by mixing TiO₂ or N-TiO₂, respectively with TOP in a flask and heating the mixture to the reflux temperature for 12 h under nitrogen atmosphere. All samples were cleaned by acetone, ethanol and water for three times to remove surface adsorbed contaminants.

2. Scanning tunneling spectroscopy measurements

The scanning tunneling microscopy and scanning tunneling spectroscopy were done in an Omicron UHV/variable temperature scanning probe microscope, at room temperature and a base vacuum of 3×10^{-11} torr. The carefully washed TiO₂ nanoparticles were drop-cast on a gold substrate and dried in N₂. The thickness is carefully controlled to obtain satisfactory conductivity for STS measurement. The *I-V* and dI/dV vs. sample bias V measurements were done by turning off the feedback mechanism at each pixel and holding the tip-sample distance constant while stepping incrementally through the voltage range in 200 steps. The *I-V* curves were measured simultaneously with the dI/dV. We obtained dI/dV at each of the 200 DC voltage bias steps by employing a modulation bias technique which requires superimposing a small AC bias over the DC voltage bias during the STS voltage bias sweep. The modulation frequency is 6 kHz and amplitude is 75 mV. The nanocrystals were deposited on gold substrates. The measurement tip is Pt/Ir. The modulation in the tunneling current dI is amplified by the STM electronics and turned into a voltage signal. The magnitude of the dIsignal for each voltage step is extracted by the lock-in amplifier and stored. We collected STS on selected areas of 1 μ m ×1 μ m size using 125×125 pixel scan resolution. A threshold of 2.5% of the maximum dI/dV value was chosen to cut the dI/dV curve, and the difference between positive and negative bias was taken to be the band gap. The threshold was chosen so that the most probable band gap of the undoped TiO₂ is 3.0 eV. The threshold dI/dV value, the intersection of the positive and negative bias voltages and the band gap determination for each pixel is automated using a home-made C++ program.

Part 2: Theoretical details

Our hybrid functional calculation is based on the mixing of screened Hartree-Fock exchange (as introduced in the HSE scheme) into the conventional PBE exchange using a mixing parameter of 0.18. Such a hybrid scheme gives a band gap for anatase TiO_2 of 3.25 eV and enthalpy of formation of 9.6 eV/TiO₂ formula. Both values are in good agreement with experimental values.

Regarding the electronic structure in Fig. 1(b), for an isolated N₀ defect, three defect levels emerge in the band gap of TiO₂, which are mainly contributed by N 2p orbitals. Each of them is spin-polarized giving rise to six spin orbitals, five of which are occupied and located close to the valence band. Only one empty spin-down orbital is located higher in the band gap. This result indicates that the N dopant on O site is weakly involved in the bonding with the neighboring Ti atoms, which is common for N doping in other oxide materials, such as ZnO^6 and SnO_2^7 . The high-lying empty spin orbital is because of the Hartree-Fock component in the hybrid functional, which enhances the spin splitting compared with conventional DFT functionals.

To calculate defect formation energy, we used the standard formalism^{8,9}. Taking the case of P-on-O (P_O) as an example, the formation energy $\Delta H(P_O) = E(P_O) - E_0 - \mu_P + \mu_O$, where E_0 is the total energy of the perfect supercell without any defect, $E(P_O)$ is the total energy of the supercell containing a P_O defect, μ_P and μ_O are the chemical potentials of P and O, respectively. μ_P is taken to be the total energy per P atom in red phosphorous. $\mu_O = \mu_O^0 + \mu'_O$, where μ_O^0 is taken to be total energy per O atom in an isolated O₂ molecule. Similarly, $\mu_{Ti} = \mu_{Ti}^0 + \mu'_{Ti}$, where μ_{Ti}^0 is taken to be total energy per Ti atom in Ti metal (*hcp* phase). To

maintain a stable TiO₂ phase, it is required that $\mu'_{Ti} + 2\mu'_O = -\Delta H(TiO_2) = -9.6 \text{ eV}^8$. Thus, μ'_O can vary between -4.8 eV to 0 eV, where $\mu'_O = 0$ eV corresponds to O-rich condition, while $\mu'_O = -4.8$ eV corresponds to Ti-rich condition.

Our DFT calculation shows that (see Fig. S4) without the presence of N, the formation energy for a P-on-Ti (P_{Ti}) defect is lower than that for a P-on-O (P_O) defect over a wide range of O chemical potential. In the presence of N dopants, however, the formation energy of a P_O defect in the neighborhood of a N_O defect can be lowered by 3.4 eV because of the new chemical bonding. As a result, under the Ti-rich condition, it is possible for a P dopant to occupy an O site.

The calculation of defect transition level, $\varepsilon(q/q')$, follows the method as described in, e.g., Refs. [9,10]. Taking P_{Ti} as an example, its $\varepsilon(0/+)$ level is calculated by

$$\varepsilon(0/+) = E(P_{Ti}^{0}) - E(P_{Ti}^{+}) - E_{VBM},$$

where $E(P_{Ti}^{0})$ and $E(P_{Ti}^{+})$ are the total energy of the supercell containing the P_{Ti} defect in neutral and 1+ charge state, respectively, and E_{VBM} is the energy of valence band maximum of bulk anatase TiO₂. Our calculation shows that P_{Ti} has a $\varepsilon(0/+)$ level between 3.24 to 3.26 eV above the VBM, where the 0.02 eV uncertainty is because of the Madelung correction¹⁰. Considering the calculated band gap of 3.25 eV, this result suggests that P_{Ti} is a shallow donor and does not introduce any deep electronic levels in the band gap.

Supplemental figures



Figure S1, SEM images of (a) N-TiO₂ (N: 2.4%) and (b) NP-TiO₂ (N: 1%, P: 3.7%). Uniform and nearly spherical TiO₂ particles with sizes of about 1 μ m were obtained for both N-doped only and NP-doped TiO₂. P doping can hardly affect the morphology of N-TiO₂ although P doping process was carried out under higher temperature after N doping.



Figure S2, High-resolution TEM images of (a) undoped TiO_2 and (b) NP- TiO_2 ; (c) and (d) show the corresponding selected area electron diffraction (SAED) patterns. The particles with crystallite sizes ranging from 5 to 10 nm can be found from undoped TiO_2 and NP- TiO_2 , indicating that the particles in **Fig. S1** may be some microspheres composed of many smaller TiO_2 particles with a diameter of 5-10 nm. The SAED patterns show that the anatase structure was retained upon doping.



Figure S3, X-ray diffraction patterns of TiO₂, N-TiO₂, NP-TiO₂, and PN-TiO2. All samples demonstrate anatase structure. The large half-peak width and low intensity of (101) diffraction peaks at 20 of 25° further confirm the microsphere of doped TiO₂ was composed of small nanoparticles.



Figure S4, Formation energy of P_{Ti} , P_O and P_O bonded to a N_O defect as a function of oxygen chemical potential.

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